

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	4526	damascene near1 (pattern structure)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:48
L2	11190	damascene and semiconductor and substrate	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:50
L3	992	2 and mask and ((light adj source) uv duv)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:51
L4	2163	2 and mask and ((light adj source) uv duv lithography)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:50
L5	58	4 and ((anti near reflective near coating) arc barc) and ((photo near active near dielectric) pad)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:56
L6	431	4 and ((anti near reflective near coating) arc barc sion) and ((photo near active near dielectric) polymer polymeric polyimide polysilsequioxane)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:51
L7	1	4 and ((anti near reflective near coating) arc barc) and (photo near active near dielectric)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 08:58
L8	1	4 and ((anti near reflective near coating) sion arc barc) and (photo near active near dielectric)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 09:01

L9	144	6 and photolithographic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:34
L10	144	9 and (method process)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 09:03
L11	9	("6242344").URPN.	USPAT	OR	ON	2005/05/27 10:29
L12	11	("5635423" "5686354" "5741626" "5801094" "5863835" "5877075" "5882996" "5904565" "5906910" "5933761" "5935762").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/05/27 10:32

L13	162	(US-20030068864-\$ or US-20030077897-\$ or US-20030129827-\$ or US-20040023453-\$ or US-20040069410-\$ or US-20040156987-\$ or US-20040166240-\$ or US-20050009290-\$ or US-20050020003-\$).did. or (US-4333227-\$ or US-4339767-\$ or US-4378630-\$ or US-4381953-\$ or US-4582565-\$ or US-4734384-\$ or US-4868617-\$ or US-4994406-\$ or US-5252848-\$ or US-5504033-\$ or US-5510648-\$ or US-5536675-\$ or US-5707896-\$ or US-5753548-\$ or US-5753967-\$ or US-5793089-\$ or US-5808347-\$ or US-5817568-\$ or US-5841166-\$ or US-5869875-\$ or US-5886382-\$ or US-5895253-\$ or US-5900663-\$ or US-5918137-\$ or US-5949104-\$ or US-5950093-\$).did. or (US-5989776-\$ or US-6001414-\$ or US-6004883-\$ or US-6008114-\$ or US-6025264-\$ or US-6034415-\$ or US-6037262-\$ or US-6048772-\$ or US-6051468-\$ or US-6054355-\$ or US-6060380-\$ or US-6071806-\$ or US-6074954-\$ or US-6091110-\$ or US-6093632-\$ or US-6100163-\$ or US-6100184-\$ or US-6137152-\$ or US-6140200-\$ or US-6144096-\$ or US-6144099-\$ or US-6153528-\$ or US-6153905-\$ or US-6180490-\$ or US-6180507-\$ or US-6180518-\$ or US-6180995-\$).did. or (US-6190978-\$ or US-6204166-\$ or US-6211063-\$ or US-6211069-\$ or US-6214696-\$ or US-6214698-\$ or US-6215152-\$ or US-6218287-\$ or US-6221727-\$ or US-6222233-\$ or US-6251763-\$ or US-6259160-\$ or US-6271552-\$ or US-6274923-\$ or US-6284657-\$ or US-6287931-\$ or US-6291298-\$ or US-6291333-\$ or US-6294423-\$ or US-6297127-\$ or US-6319820-\$ or US-6329280-\$ or US-6348407-\$ or US-6348733-\$ or US-6358842-\$ or US-6365952-\$ or US-6372635-\$).did. or (US-6376366-\$ or US-6380073-\$ or US-6383913-\$ or US-6399432-\$ or US-6399449-\$ or US-6413827-\$ or US-6429116-\$ or US-6429129-\$ or US-6436824-\$ or US-6440819-\$ or US-6461934-\$ or US-6476445-\$ or US-6488061-\$ or US-6495903-\$ or US-6509267-\$ or US-6514860-\$ or US-6518176-\$ or US-6521072-\$ or US-6
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L14	6	"6506979"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L15	13	"5334488"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L16	3	"6521328"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L17	9	"6349456"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:29
L18	26	14 15 16 17	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:30
L19	25	18 not 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 12:30
L20	53	9 and (polyimide (fluorinated adj polyimide) polysilsequioxane benzocyclobutene (parlene adj (n f)) (amorphous adj polytetrafluoroethylene))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:52
L21	2959	2 and mask and ((light adj source) uv duv photolithographic lithography)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:50

L22	873	21 and ((anti near reflective near coating) arc barc sion)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:52
L23	236	22 and (polyimide (fluorinated adj polyimide) polysilsequioxane benzocyclobutene (parlene adj (n f)) (amorphous adj polytetrafluoroethylene))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:52
L24	118	23 and (substrate with conductive)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:54
L25	174	23 and (substrate with (conductive metal))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/05/27 14:53